

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 264197US0PCT		SERIAL NO. 10/519,837	
LIST OF REFERENCES CITED BY APPLICANT		APPLICANT					
		Shinsuke SADAMITSU, et al.					
		FILING DATE January 11, 2005		GROUP			
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
MW	AO	1087041	03/28/01	EP	YES	NO	
MW	AP	5-144827	06/11/93	JP			NO
	AQ						
	AR						
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
MW	AW	BABICH, V.M. et al., 'Generation of thermal donors as a result of one- and two-step annealing of silicon crystals with large and small carbon concentrations'. Semiconductors, Vol. 30, No. 5, pages 417 to 419, May 1996.					
MW	AX	KODATE, Junichi et al., Suppression of Substrate Crosstalk in Mixed-Signal Complementary MOS Circuits Using High-Resistivity SIMOX (Separation by Implanted O ₂) Wafers, Japanese Journal of Applied Physics, Part 1, Vol.39, No.4B, pages 2256 to 2260, April 2000.					
MW	AY	WIJARANAKULA, W. et al., 'A Formation of Crystal Defects in Carbon-Doped Czochralski-Grown Silicon after a Three-Step Internal Gettering Anneal', Journal of Electrochemical Society, Vol.138, No.7, pages 2153 to 2159, July 1991.					
MW	AZ	GAWORZEWSKI P. et al., "Oxygen-Related Donors Formed at 600°C in Silicon in Dependence on Oxygen and Carbon Content", Phys.Stat.Sol. (a), Vol.77, No.2, pages 571 to 582, 1983				<input type="checkbox"/> Additional References sheet(s) attached	
Examiner /Mary Wilczewski/					Date Considered 10/30/2006		
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							